

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

Listing of Claims:

1. (Currently Amended) A method for removing a resist pattern, comprising:
forming a metal film over a substrate;
forming a resist pattern of a positive resist composition containing a photosensitizer over the metal film;
etching the metal film by using the resist pattern;
irradiating the resist pattern with a light having a photosensitive wavelength region of the photosensitizer after etching the metal film; and
removing the resist pattern by using a resist stripper which dissolves and removes the resist pattern.

2. (Currently Amended) A method for removing a resist pattern, comprising:
forming a metal film over a substrate;
forming a resist pattern of a positive resist composition containing a photosensitizer over the metal film;
etching the metal film by using the resist pattern;
removing the resist pattern by using a resist stripper which dissolves and removes the resist pattern;
~~irradiating an unprocessed portion~~ a residue of the resist pattern with a light having a photosensitive wavelength region of the photosensitizer after removing the resist pattern; and
~~treating the unprocessed portion~~ removing the residue of the resist pattern by using a developer.

3. (Currently Amended) A method for manufacturing a semiconductor device, comprising:

- forming a metal film over a substrate;
- forming a resist pattern of a positive resist composition containing a photosensitizer over the metal film;
- etching the metal film by using the resist pattern;
- irradiating the resist pattern with a light having a photosensitive wavelength region of the photosensitizer after etching the metal film; and
- ~~performing a resist-removing the resist pattern by using a resist stripper which dissolves and removes the resist pattern on the resist pattern.~~

4. (Currently Amended) A method for manufacturing a semiconductor device, comprising:

- forming a metal film over a substrate;
- forming a resist pattern of a positive resist composition containing a photosensitizer over the metal film;
- etching the metal film by using the resist pattern;
- removing the resist pattern by using a resist stripper which dissolves and removes the resist pattern;
- ~~irradiating an unprocessed portion~~ a residue of the resist pattern with a light having a photosensitive wavelength region of the photosensitizer after removing the resist pattern; and
- ~~treating the unprocessed portion~~ removing the residue of the resist pattern by using a developer after irradiating the resist pattern with the light having the photosensitive wavelength region of the photosensitizer.

5. (Previously Presented) A method for removing a resist pattern according to claim 1, wherein the positive resist composition containing the photosensitizer is a diazonaphthoquinone (DNQ)-novolac resin type, and

wherein the photosensitizer is diazonaphthoquinone (DNQ).

6. (Previously Presented) A method for removing a resist pattern according to claim 2, wherein the positive resist composition containing the photosensitizer is a diazonaphthoquinone (DNQ)-novolac resin type, and wherein the photosensitizer is diazonaphthoquinone (DNQ).

7. (Previously Presented) A method for manufacturing a semiconductor device according to claim 3, wherein the positive resist composition containing the photosensitizer is a diazonaphthoquinone (DNQ)-novolac resin type, and wherein the photosensitizer is diazonaphthoquinone (DNQ).

8. (Previously Presented) A method for manufacturing a semiconductor device according to claim 4, wherein the positive resist composition containing the photosensitizer is a diazonaphthoquinone (DNQ)-novolac resin type, and wherein the photosensitizer is diazonaphthoquinone (DNQ).

9. (Previously Presented) A method for removing a resist pattern according to claim 2, wherein the metal film forms an electrode of a thin film transistor.

10. (Previously Presented) A method for manufacturing a semiconductor device according to claim 3, wherein the metal film forms an electrode of a thin film transistor.

11. (Previously Presented) A method for manufacturing a semiconductor device according to claim 4,

wherein the metal film forms an electrode of a thin film transistor.

12-16. (Canceled)

17. (Previously Presented) A method for manufacturing a semiconductor device according to claim 3, wherein a range of an exposure period of time to irradiate the resist pattern with the light having the photosensitive wavelength region of the photosensitizer is from 1 seconds to 30 seconds.

18. (Previously Presented) A method for manufacturing a semiconductor device according to claim 4, wherein a range of an exposure period of time to irradiate the resist pattern with the light having the photosensitive wavelength region of the photosensitizer is from 1 seconds to 30 seconds.

19. (Canceled)

20. (Previously Presented) A method for removing a resist pattern according to claim 1, wherein the substrate is selected from the group consisting of a glass, a quartz, a semiconductor, a plastic, a plastic film, a metal, a glass-epoxy resin, and a ceramic.

21. (Previously Presented) A method for removing a resist pattern according to claim 2, wherein the substrate is selected from the group consisting of a glass, a quartz, a semiconductor, a plastic, a plastic film, a metal, a glass-epoxy resin, and a ceramic.

22. (Previously Presented) A method for manufacturing a semiconductor device according to claim 3, wherein the substrate is selected from the group consisting of a glass, a quartz, a semiconductor, a plastic, a plastic film, a metal, a glass-epoxy resin, and a ceramic.

23. (Previously Presented) A method for manufacturing a semiconductor device according to claim 4, wherein the substrate is selected from the group consisting of a glass, a quartz, a semiconductor, a plastic, a plastic film, a metal, a glass-epoxy resin, and a ceramic.

24. (Previously Presented) A method for removing a resist pattern according to claim 1, wherein the metal film comprises a material selected from the group consisting of aluminum, titanium, molybdenum, tantalum, and tungsten.

25. (Previously Presented) A method for removing a resist pattern according to claim 2, wherein the metal film comprises a material selected from the group consisting of aluminum, titanium, molybdenum, tantalum, and tungsten.

26. (Previously Presented) A method for manufacturing a semiconductor device according to claim 3, wherein the metal film comprises a material selected from the group consisting of aluminum, titanium, molybdenum, tantalum, and tungsten.

27. (Previously Presented) A method for manufacturing a semiconductor device according to claim 4, wherein the metal film comprises a material selected from the group consisting of aluminum, titanium, molybdenum, tantalum, and tungsten.

28. (New) A method for removing a resist pattern according to claim 1, wherein the resist stripper has a mixture of 2-aminoethanol and a glycol ether as a composition.

29. (New) A method for removing a resist pattern according to claim 2, wherein the resist stripper has a mixture of 2-aminoethanol and a glycol ether as a composition.

30. (New) A method for manufacturing a semiconductor device according to claim 3, wherein the resist stripper has a mixture of 2-aminoethanol and a glycol ether as a composition.

31. (New) A method for manufacturing a semiconductor device according to claim 4, wherein the resist stripper has a mixture of 2-aminoethanol and a glycol ether as a composition.

32. (New) A method for removing a resist pattern according to claim 1, wherein the light has a multiple wavelengths within the range of photosensitive wavelength region of the photosensitizer.

33. (New) A method for removing a resist pattern according to claim 2, wherein the light has a multiple wavelengths within the range of photosensitive wavelength region of the photosensitizer.

34. (New) A method for manufacturing a semiconductor device according to claim 3, wherein the light has a multiple wavelengths within the range of photosensitive wavelength region of the photosensitizer.

35. (New) A method for manufacturing a semiconductor device according to claim 4, wherein the light has a multiple wavelengths within the range of photosensitive wavelength region of the photosensitizer.